ALD 2020 - AVS 20th International Conference on Atomic Layer Deposition

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Title	ALD 2020 - AVS 20th International Conference on Atomic Layer Deposition
When	So, 28. Juni 2020 - Mi, 1. Juli 2020

Description

ALD 2020 - AVS 20th International Conference on Atomic Layer Deposition

The AVS 20th International Conference on Atomic Layer Deposition (ALD 2020) featuring the 7th International Atomic Layer Etching Workshop (ALE 2020) will be a three-day meeting dedicated to the science and technology of atomic layer controlled deposition of thin films and now topics related to atomic layer etching.

Since 2001, the ALD conference has been held alternately in the United States, Europe and Asia, allowing fruitful exchange of ideas, know-how and practices between scientists. This year, the ALD conference will again incorporate the Atomic Layer Etching 2020 Workshop (ALE 2020), so that attendees can interact freely. The conference will take place Sunday, June 28-Wednesday, July 1, 2020, at the International Convention Center in Ghent, Belgium.

Please learn more about htis evennt by following link:

https://ald2020.avs.org/

Venue - Ghent

Location	Ghent
City	Ghent
Country	BE